Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1017	(438/258).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/01 06:25
L2	276	(438/596).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/01 06:25
L3	2374	257/e21.209.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/10/01 06:25
L4	815	257/e21.336.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/10/01 06:26
L5	5043	(((floating adj gate) with (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/10/01 06:26
L6	645	(((floating adj gate) with (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/10/01 06:26
L7	242	(((floating adj gate) with (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain).clm.	US-PGPUB	OR	ON	2007/10/01 06:27

L8	7	((((floating adj gate) with (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain) and (first adj dopant) and (second adj dopant)). clm.	US-PGPUB	OR	ON	2007/10/01 06:28
S1	1946	(438/257).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/29 08:53
S2	1173	(438/592).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/07 08:20
S3	1265	(438/592).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/07 08:21
S4	996	(438/592).CCLS.	USPAT	OR	OFF	2005/09/07 08:21
S5	2219	(438/257).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/07 08:21
S6	1306	(438/257).CCLS.	USPAT	OR	OFF	2007/10/01 06:25
S7	1	("6737320").PN.	USPAT	OR	OFF	2007/07/05 09:51
S9	2298	(438/257).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/29 08:53
S10	4027	((floating adj gate) with (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/10/01 06:26

S13	1	10/649050	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/27 07:13
S14	2	10/230523	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/27 07:13
S15	2	(("7067871") or ("5841161")).PN.	USPAT	OR	OFF	2007/06/28 15:02
S16	2	(("6111287") or ("5841161")).PN.	USPAT	OR	OFF	2007/06/28 15:02
S17	525	((floating adj gate) near (dop\$5 or implant\$)) and ((dielectric or insulating or oxide) adj (layer or film)) and (control adj gate) and source and drain	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/28 16:56
S18 -	4	(("6737320") or ("5841161") or ("6111287") or ("7067871")).PN.	USPAT	OR	OFF	2007/07/05 11:11
S19	1947	((alumium adj oxide) or alumina or ("Al.sub.2 O.sub.3")) and ((atomic adj layer adj deposition) or ("ALD"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/05 11:12
S20	50	((alumium adj oxide) or alumina or ("Al.sub.2 O.sub.3")) near ((atomic adj layer adj deposition) or ("ALD"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/05 11:13
S21	42	(((alumium adj oxide) or alumina or ("Al.sub.2 O.sub.3")) near ((atomic adj layer adj deposition) or ("ALD"))) and @ad<="20050302"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/05 11:14
S22	8	("3731163" "4682407" "4914046" "5691560" "5841161" "6111287").PN. OR ("6737320"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/07/05 12:12

S23	8	("3731163" "4682407" "4914046" "5691560" "5841161" "6111287").PN. OR ("6737320").	US-PGPUB; USPAT; USOCR	OR	ON	2007/07/05 13:05
		URPN.	OSOCIC			

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